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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/622,855	07/18/2003	Amitay Levi	2102397-992720	2925
26379	7590 12/14/2004		EXAMINER	
GRAY CARY WARE & FREIDENRICH LLP			NGUYEN, CUONG QUANG	
	SITY AVENUE O, CA 94303-2248		ART UNIT PAPER NUMBER	
	-, · · · · · · · · · · · · · · · · ·		2811	

DATE MAILED: 12/14/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Summany	10/622,855	LEVI ET AL.				
Office Action Summary	Examiner	Art Unit	j			
· · · · · · · · · · · · · · · · · · ·	Cuong Q Nguyen	2811	- Pr			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence ad	dress			
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply of 18 NO period for reply is specified above, the maximum statutory period we failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	66(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	ely filed s will be considered timely the mailing date of this co O (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on	_•					
2a) ☐ This action is FINAL. 2b) ☒ This	This action is FINAL. 2b) This action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	33 O.G. 213.				
Disposition of Claims						
4) Claim(s) 1-35 is/are pending in the application.						
4a) Of the above claim(s) 9-13 and 24-35 is/are	withdrawn from consideration.					
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-8 and 14-23</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or	r election requirement.					
Application Papers						
9) The specification is objected to by the Examine	г.					
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correct	ion is required if the drawing(s) is obj	ected to. See 37 CF	R 1.121(d).			
11) The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PT	O-152.			
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority 	s have been received. s have been received in Applicati	on No	Stane			
application from the International Bureau		,	Ciago			
* See the attached detailed Office action for a list	` '//	d.				
Attachment(s)		,				
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) 	4) L Interview Summary Paper No(s)/Mail Da	•				
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 04-21-04 & 05-03-04		atent Application (PTC) - 152)			

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DETAILED ACTION

Election/Restriction

1. Applicant's election without traverse of Embodiment 1 (Fig.1a to Fig.1b and Fig.3a to Fig.3k and Fig.4) is acknowledged. Claims 1-8 and 14-23 read on the elected Embodiment, so claims 9-13 and 24-28 are withdrawn from consideration.

Claim Rejections - 35 USC § 103

2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-8 and 14-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hsieh (US 2004/0087084) in view of Sung et al. (US 6,331,721).

Regarding claims 1, 2, Hsieh discloses a non-volatile memory cell comprising: a p-type silicon substrate (110); a n-type first region (154) and a n-type second region (226) formed in the substrate; a channel region formed between first and second regions, the channel region having a first portion close to the first region and a second portion close to the second region; a control gate (190) insulated from the second portion of the channel region; a floating gate (166) adjacent to the control gate and insulated

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therefrom, and insulated from the first portion of channel region, floating gate having a tip adjacent to the control gate; an erase gate (208) insulated from the control gate and the tip of the floating gate; an insulating material (204) between tip and erase gate permitting charges to tunnel from the tip to the erase gate (lines 1-7 col.1 of page 5). See Hsieh's Fig.16B.

Hsieh does not explicitly teach that the silicon substrate is a single crystalline silicon substrate.

It is conventional and also taught by Sung et al. (col.5b lines 1-6) that a single crystalline silicon material is art recognized material for forming the substrate in the semiconductor memory device because it is convenient and available in the semiconductor field.

So, it would have been obvious to one of ordinary skill in the art to form the substrate of single crystalline silicon as taught by Sung et al. into Hsieh's device.

Regarding claim 3, as shown in Hsieh's Fig.16B, the substrate (110) has a substantially planar surface and wherein first and second regions and channel region are along the planar surface.

Regarding claim 4, Hsieh teaches that the insulating material is silicon oxide (lines 13-19 col.2 of page 4) which is known in the art as silicon dioxide.

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Regarding claim 5, Hsieh teaches the floating gate is insulated from the planar surface by a layer (114) of silicon oxide (lines 18-23 col.2 of page 2) which is known in the art as silicon dioxide.

Regarding claim 6, Hsieh teaches the floating gate is insulated from the control gate by a layer (174) of nitride (lines 43-48 col.2 of page 3) which is known in the art as silicon nitride.

Regarding claim 7, Hsieh teaches the control gate is insulated from the planar surface by a layer (174) of silicon oxide (lines 43-48 col.2 of page 3) which is known in the art as silicon dioxide.

Regarding claim 8, as shown in Hsieh's Fig.16B, the floating gate is capacitively coupled to the first region.

Regarding claims 14-22, as shown in Hsieh's Fig.16B, the cells in the same row have their first regions (154) connected together.

Regarding claim 23, as shown in Hsieh's Fig.16A, the cells in the same column have their control gate (the wordline) connected together and have erase gates connected together.

Conclusion

3. Papers related to this application may be submitted to Technology center (TC) 2800 by facsimile transmission. Papers should be faxed to TC 2800 via the TC 2800 Fax center located in Crystal Plaza 4, room 4-C23. The faxing of such papers must

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conform with the notice published in the Official Gazette, 1096 OG 30 (November 15,

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1989). The Group 2811 Fax Center number is (703) 872-9306. The Group 2811 Fax

Center is to be used only for papers related to Group 2811 applications.

4. Any inquiry concerning this communication or any earlier communication from

the Examiner should be directed to CUONG Q NGUYEN whose telephone number is

(571) 272-1661. The Examiner is in the Office generally between the hours of 6:30 AM

to 5:00 PM (Eastern Standard Time) Monday through Thursday. If attempts to reach the

examiner by telephone are unsuccessful, the examiner's supervisor Eddie Lee who can

be reached on (571) 272-1732.

Cuơng Nguyen

Primary examiner

11/29/04